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(54) **Title:** SUBSTRATE SUPPORTING APPARATUS

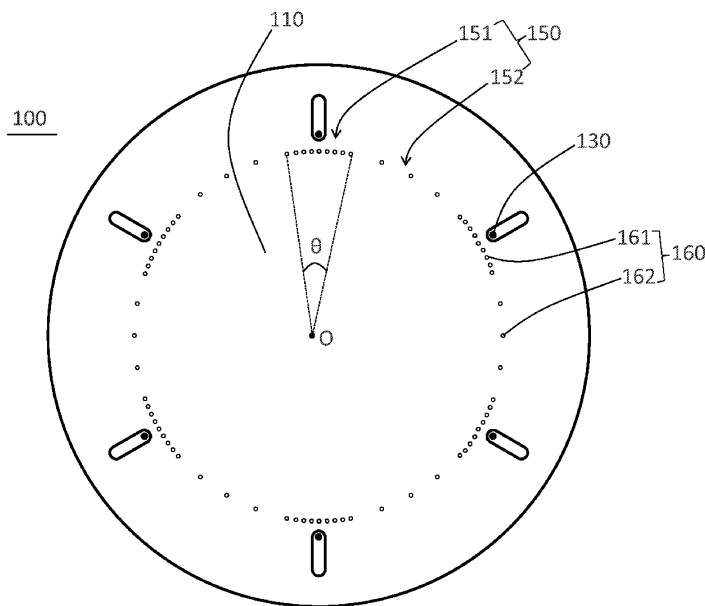


FIG 2

(57) **Abstract:** A substrate supporting apparatus having a spin chuck (100) and a plurality of locating pins (130) is provided. The spin chuck (100) configured to support and rotate a substrate (001) has a supporting surface (110). The locating pins (130) are disposed at the periphery of the supporting surface (110) for limiting the substrate (001) horizontal displacement. The supporting surface (110) defines a first annular region (150). The first annular region (150) is divided into a plurality of pin regions (151) and a plurality of non-pin regions (152). The pin regions (151) and the non-pin regions (152) are arranged alternatively in a circumferential direction of the first annular region (150). Each of the pin regions (151) is corresponding to one locating pin (130). A plurality of Bernoulli holes (160) are set in the first annular region (150) and is configured as an uneven structure in the first annular region (150) so as to supply stronger gas flow in the pin regions (151) than in the non-pin regions (152).

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